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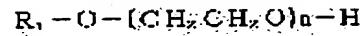
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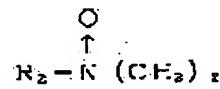
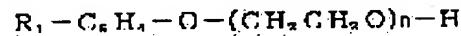
## (54) LIQUID BLEACHING AGENT COMPOSITION

### (57)Abstract:

**PROBLEM TO BE SOLVED:** To obtain the subject composition having a specific composition containing an organic peracid precursor and having high bleaching effect and excellent storage stability and low-temperature solution stability.



**SOLUTION:** This composition contains (A) a surfactant expressed by formulas I, II, etc., ( $\text{R}_1$  is an 8-18C straight or branched-chain alkyl, alkenyl, etc.; ( $n$ ) is 2-30) and (B) a surfactant selected from the surfactants of formulas III, IV, etc., ( $\text{R}_2$  is an 8-18C branched-chain alkyl, alkenyl, etc.), a straight-chain alkylbenzene sulfonic acid salt, an  $\alpha$ -olefin sulfonic acid salt and a polyoxyethylene alkyl or alkenylsulfuric acid ester salt at an A/B weight ratio of 1/0 to 10/1 and the total amount (A+B) of 5-30wt.% and further contains (C) 0.5-10wt.% of  $\text{H}_2\text{O}_2$ , (D) 0.2-5wt.% of an organic peracid precursor of the formula  $\text{R}_3\text{COO}-\text{C}_6\text{H}_4-\text{Z}$  ( $\text{R}_3$  is a 7-12C straight-chain alkyl; Z is COOH, SO<sub>3</sub>H, etc.) and (E) 0.001-5wt.% of an organic peroxide of the formula  $\text{R}_4\text{COOH}$  ( $\text{R}_4$  is a 2-12C straight or branched-chain alkyl). The pH of the composition is adjusted to 2.5-4.5.



I

II

III

IV

V

## LEGAL STATUS

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